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INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Attorney Docket No.: 4303-1009

August 8, 2006

Application No.:
NEW NATIONAL PHASE

10/588,766

Applicant: Harald KRAUS et al.

Filing Date:

Group Art Unit: 1792

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EXAMINER: DATE CONSIDERED 01/21/2008

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

^{*} English language abstract provided for the Examiner's convenience